Amendments to the Specification

Please replace the paragraph beginning at page 8, line 1 with the following rewritten paragraph:--

As has been indicated above, the overcoat layer 108 of the present invention is thinner and denser than the low energy magnetron sputtered layer 30, and it is fabricated such that carbon ion implantation into the magnetic layer 26 is minimized. To accomplish this, the overcoat layer 108 is fabricated utilizing a device that produces an ion beam that has an ion deposition energy gradient. Specifically, the fabrication of the overcoat layer 108 is commenced with the deposition of an initial overcoat layer portion 112 with a low energy ion beam, such as [[a]] from approximately 10 to approximately 20 eV ~~ion beam~~, which is generally the energy level of the low energy magnetron sputtering process of the prior art, as depicted in Fig. 1. Thereafter, as the deposition of the initial overcoat layer portion 112 progresses, the overcoat layer 112 increases in thickness upon the surface of the magnetic layer 26, and due to the relatively low deposition beam energy level, implantation of overcoat layer ions into the magnetic layer 26 is minimized. After the initial overcoat layer thickness is deposited at the low energy level, the energy level of the beam is increased to deposit an intermediate overcoat layer portion 116. The higher energy ions will penetrate more deeply into the surface layer, as has been described hereabove with regard to prior art disk 50; however, because the initial surface layer 112 has been formed of overcoat material, the higher energy overcoat ions penetrate only into the pre-existing initial overcoat layer portion 112. Thus, as the build up of the intermediate overcoat layer portion 116 progresses, the total overcoat layer generally both becomes thicker with overcoat ions that remain on its surface, as well as denser with higher energy overcoat ions that become implanted within the thickness of the initial overcoat layer. Thereafter, a subsequent overcoat layer portion 118 may be deposited with a still higher ion beam energy level. Again,

these higher energy overcoat ions penetrate into the surface of the overcoat layer 108. However, due to the thickness of the existing overcoat layer the high energy ions become implanted into both the initial and intermediate overcoat layer portions and do not penetrate into the magnetic layer 26. A typical DLC overcoat layer density of the present invention is between approximately 2.0 g/cm^3 to approximately 2.9 g/cm^3.--